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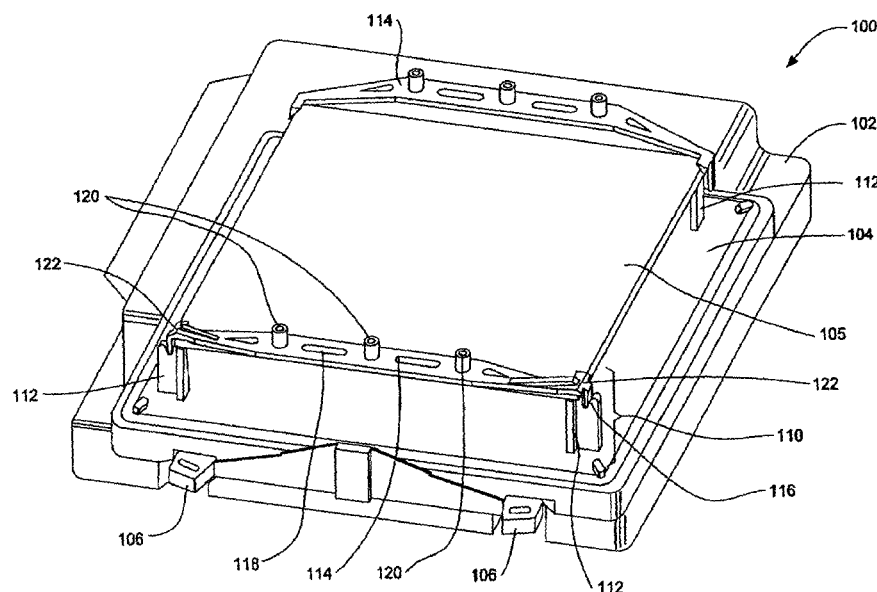
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(54) Title: SMIF CONTAINER INCLUDING AN ELECTROSTATIC DISSIPATIVE RETICLE SUPPORT STRUCTURE



(57) Abstract: The present invention is a support structure for supporting a reticle or silicon wafer (105). The support structure includes a support column (110) and a retaining structure (114). In addition to retaining a wafer, the present invention also creates a discharge path to remove electrostatic charges from the wafer. The retaining structure mechanically engages each support column to create a discharge path from the wafer to a ground.



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